

L Number	Hits	Search Text	DB	Time stamp
1	52869	(electron adj beam) and substrate	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/26 14:31
2	15257	((electron adj beam) and substrate) and stage	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/26 14:31
3	104	(((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/26 14:32
4	55	(((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area) and bias	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/26 14:32
5	1	((((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area) and bias) and (bias adj voltage) and (bias near4 level)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/26 14:33
-	50081	(electron adj beam) and substrate	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/26 14:31
-	14196	((electron adj beam) and substrate) and stage	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/26 14:31
-	2841	((electron adj beam) and substrate) and stage) and focus	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/22 11:14
-	98	((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/22 11:15
-	96	(((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/26 14:31
-	96	(((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/22 11:15
-	52	(((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area) and bias	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/26 14:32
-	25	((((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area) and (bias adj voltage)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/22 11:16
-	25	((((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area) and bias) and (bias adj voltage)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/22 11:17
-	1	((((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area) and bias) and (bias adj voltage)) and (bias near4 level)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/08/26 14:32

-	25	(((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area) and bias) and (bias adj voltage)) and voltage	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/22 11:39
-	25	(((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area) and bias) and (bias adj voltage)) and level	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/22 14:04
-	6	(((((electron adj beam) and substrate) and stage) and focus) and (surface adj charge)) and area) and bias) and (bias adj voltage)) and level) and flood	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/22 14:13
-	1	"20020130260"	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/22 14:15